

Serial No.: 10/605,108



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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

International patent application of

Docket No.: FIS920030183US1

Dureseti Chidambarao, et al.

Serial No.: 10/605,108

Group Art Unit: No. 2814

Filed: September 9, 2003

Examiner: Pham, Long

For: **METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI ON SIGE
SUBSTRATE**

Mail Stop: Non-final amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE TO RESTRICTION REQUIREMENT

Sir:

In response to the Restriction Requirement dated March 5, 2004, Applicants elect claims 1-18, without traverse.

Applicants believe that no extensions of time or fees for net addition of claims are required at this time. However, if additional extensions of time are necessary to prevent abandonment of this application, then such extensions of time are hereby petitioned under 37 C.F.R. §1.136(a), and any fees required therefor (including fees for net addition of claims) are hereby authorized to be charged to International Business Machines Corporation's deposit Account No. 09-0458.